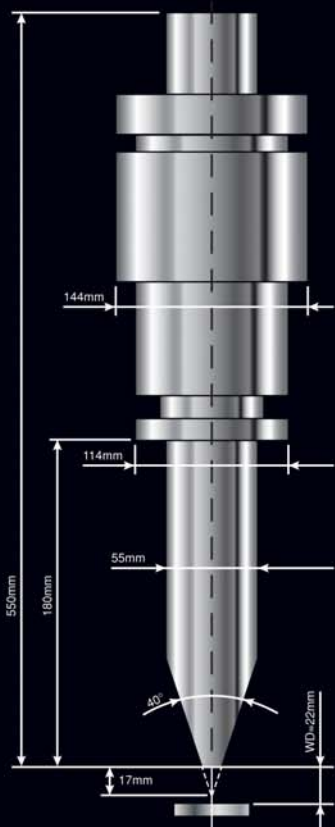




High Resolution Focused Ion Beam



FIB 30 Specification

Ion column

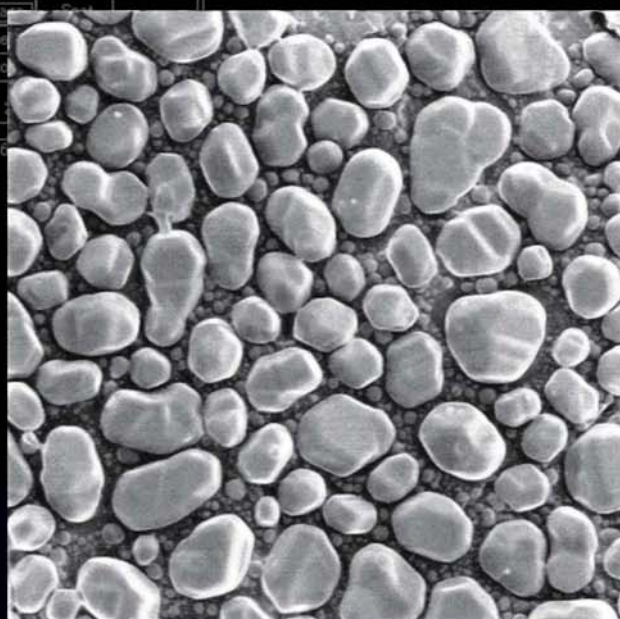
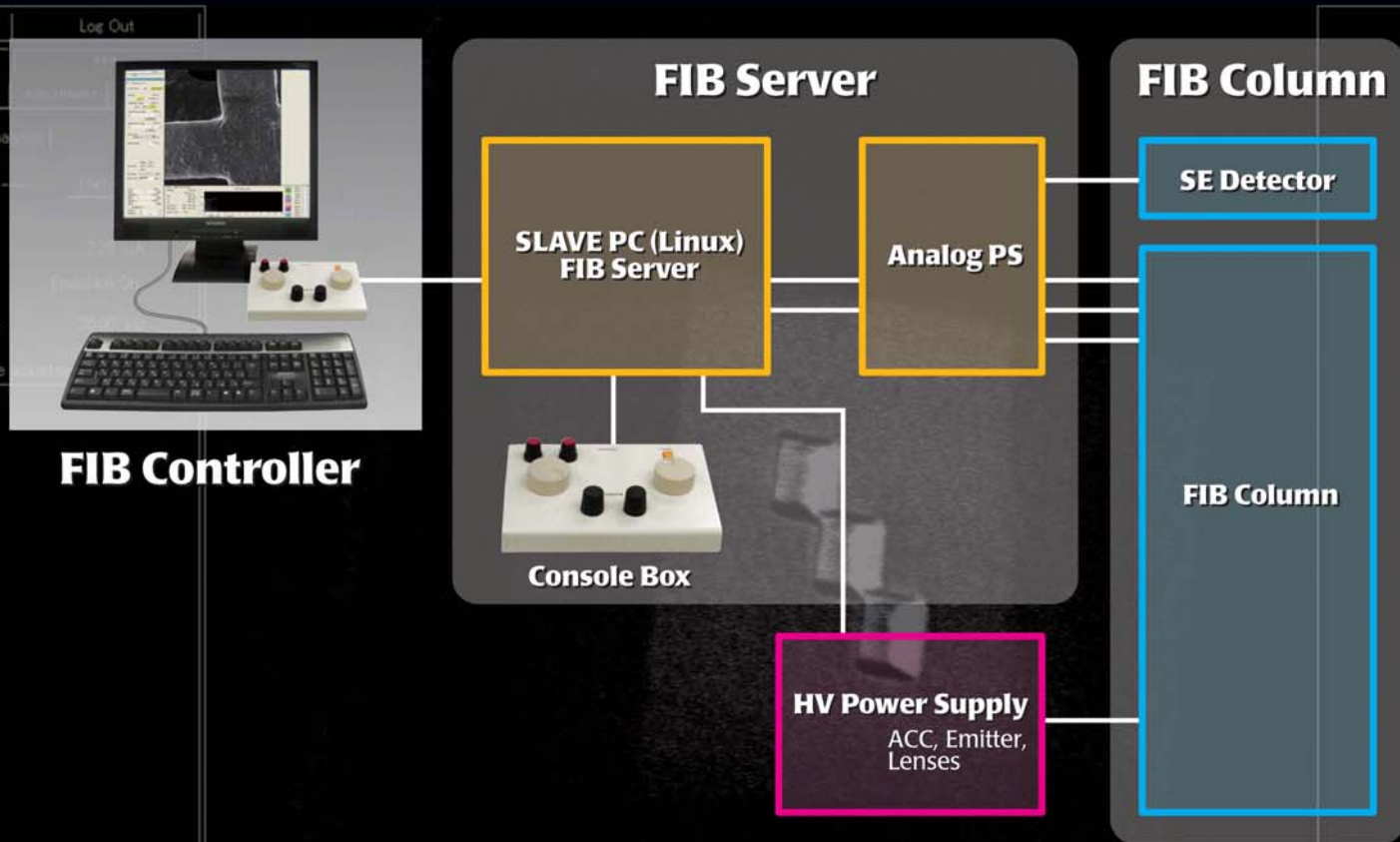
- Ion Source Ga Liquid Metal Ion Source
- Acceleration Voltage ... 2 – 30kV
(optional up to 40kV)
- Beam Current 0.2pA – 20nA
(optional up to 50nA)
- Resolution $\leq 4\text{nm}$ at 30kV (Gold on Carbon Sample)
- Aperture 4-position Manual Control
(10-position Optional Motor Control)
- Beam Blanker Standard, External Control Possible
- Image 256 × 256 – 2,048 × 2,048
- Dwell Time 100nsec – 1,000sec/pixel

Electronics

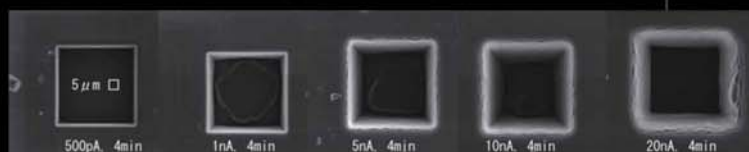
- FIB Server Linux/Pentium M
- FIB Controller PC Windows XP
- High Voltage PS Acc, CL,OL, Emitter Controller

Specifications are subject to change without notice.

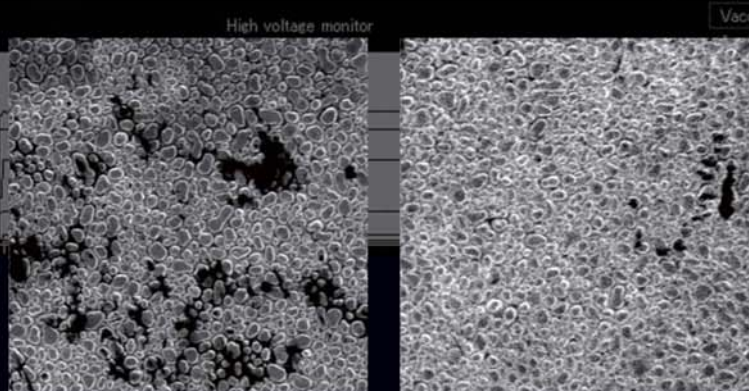
FIB 30 Column and Controller



Acceleration Voltage 30kV, 0.3pA,
Gold on Carbon Sample, Field of View 4µm



5µm Square, 4 minutes Etching with 0.5 – 20nA Ga Ion Beam



Acceleration Voltage 10kV, 5pA,
Gold on Carbon Sample,
Field of View 15µm

Acceleration Voltage 5kV, 2pA,
Gold on Carbon Sample,
Field of View 15µm